FIG. 1

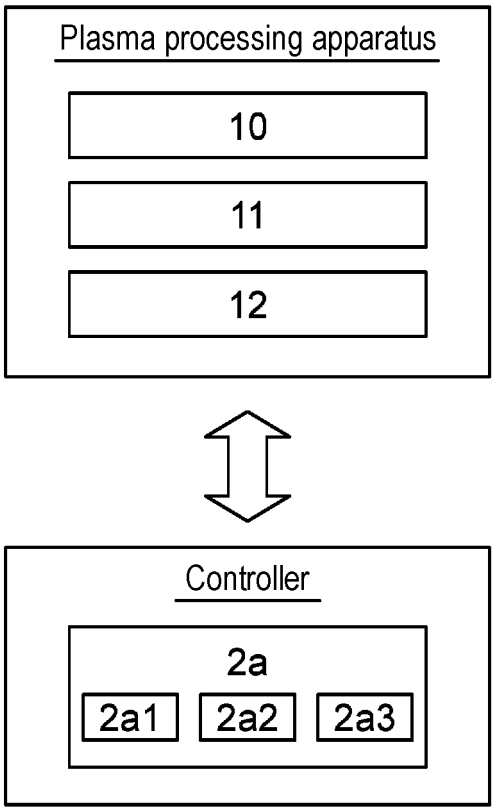

Plasma processing apparatus
10
11
12
Controller
2a
2a1
2a2
2a3

FIG. 2

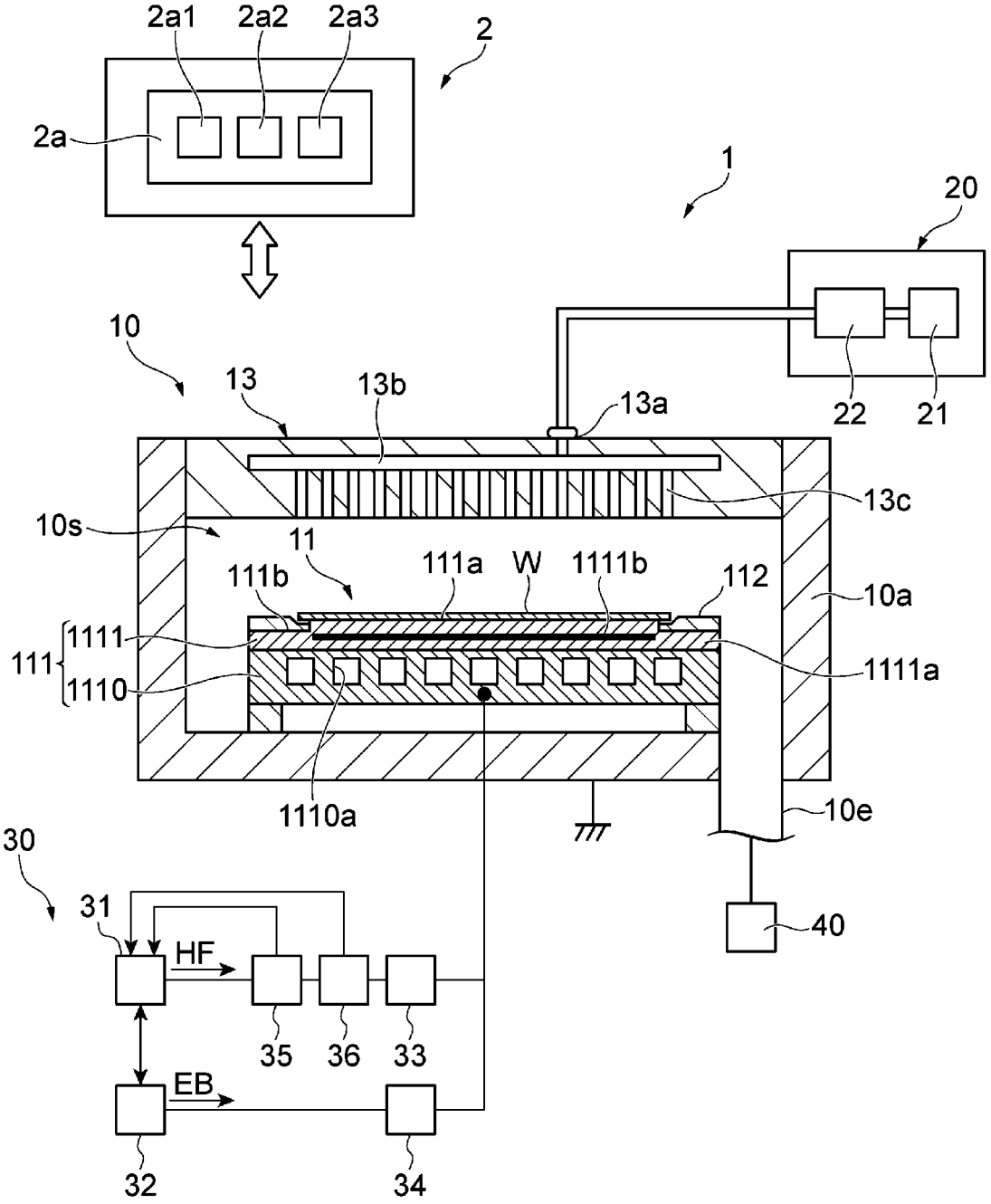

2a1
2a2
2a3
2
2a
1
20
10
13
13b
13a
22
21
13c
10s
11
111b
111a
W
1111b
112
10a
111
1111
1110
1111a
1110a
10e
30
31
HF
35
36
33
40
EB
32
34

FIG. 3

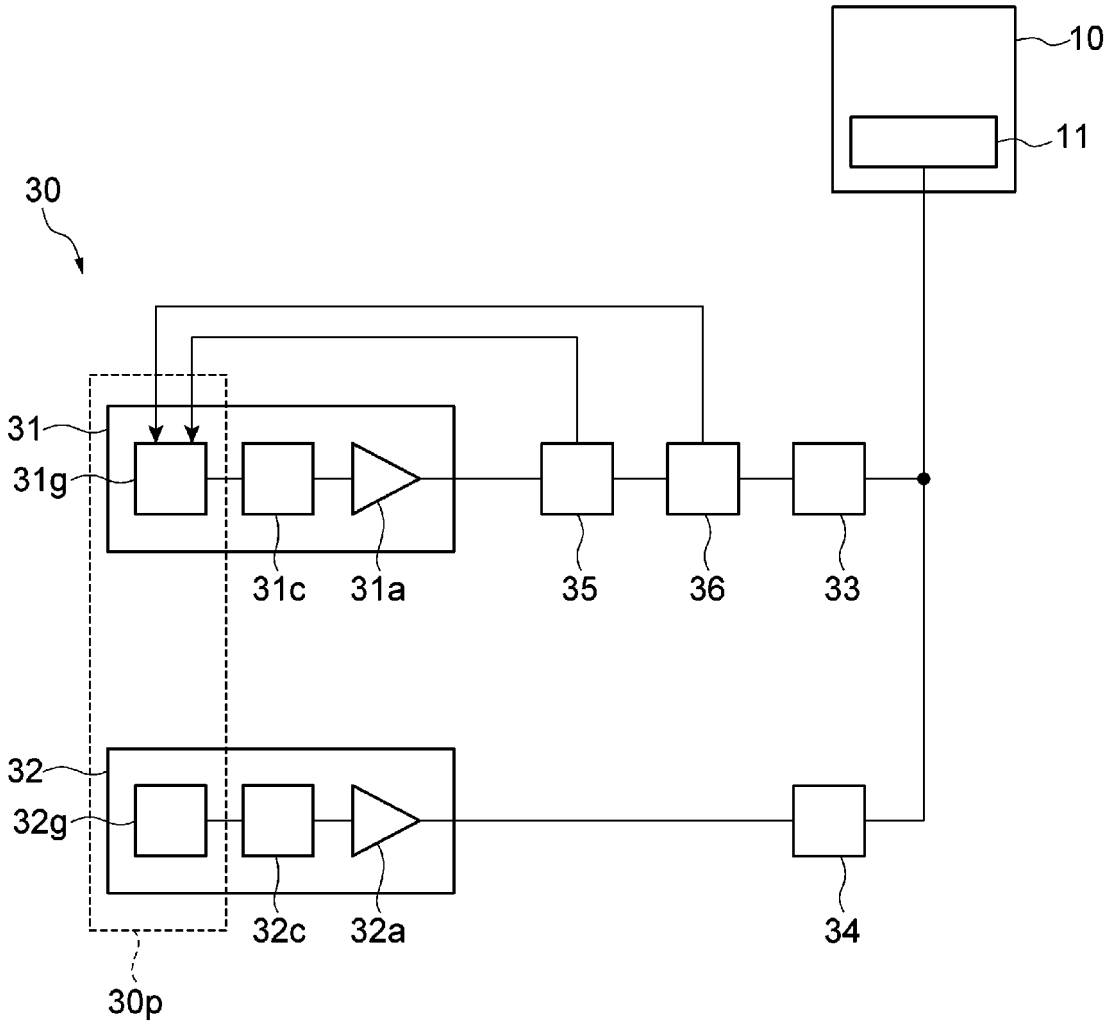


FIG. 4

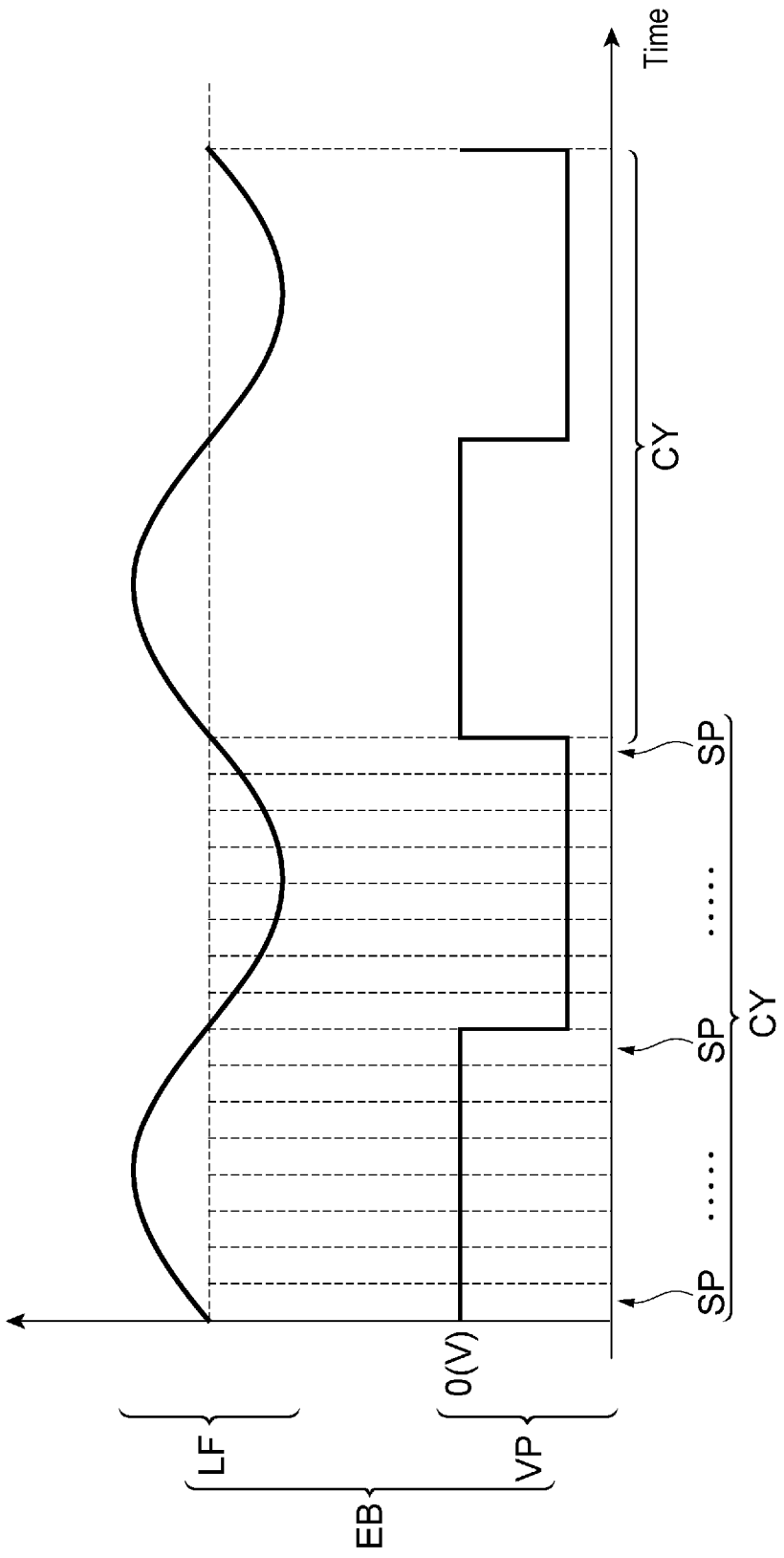


FIG. 5

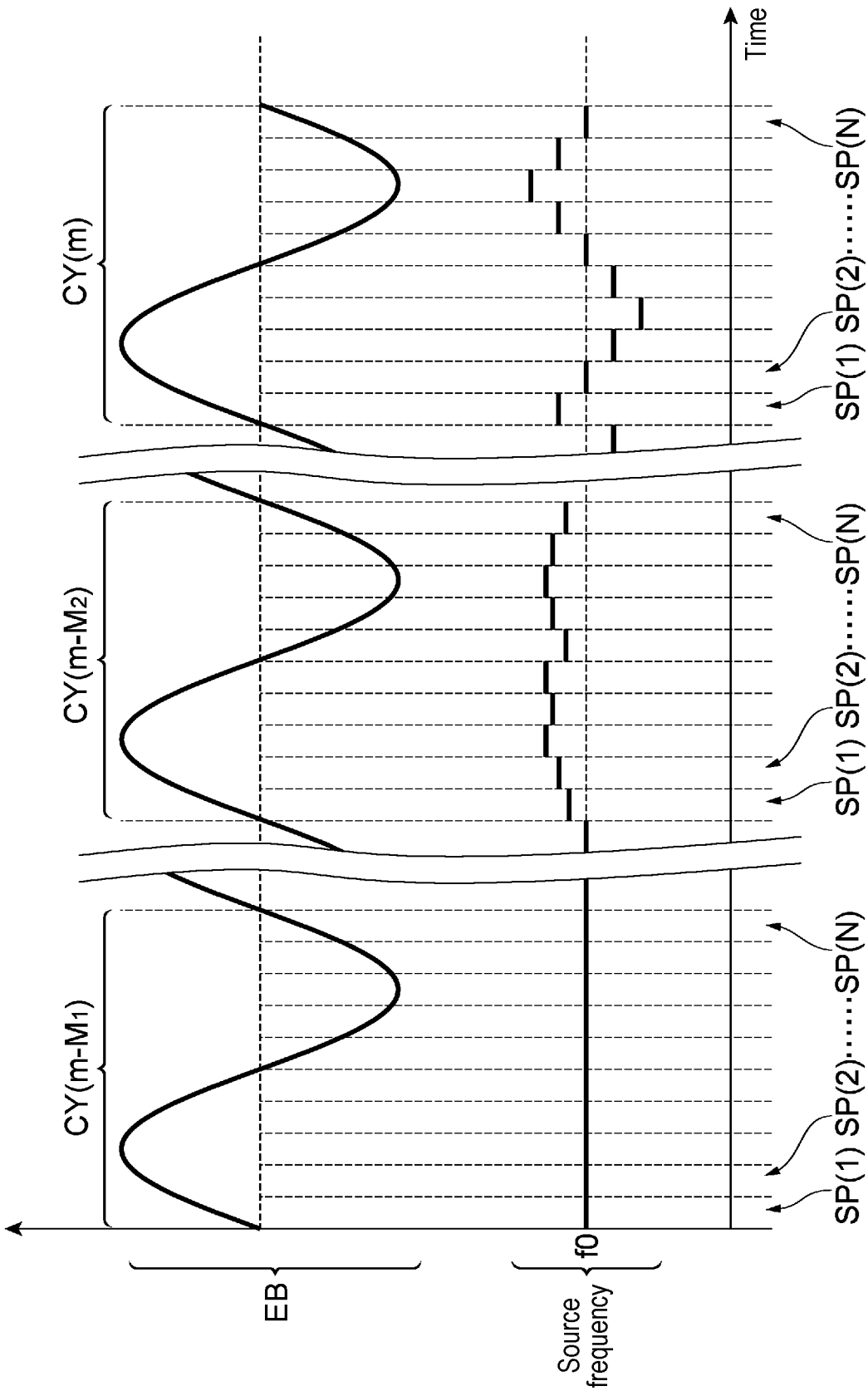

Time
CY(m)
CY(m-M2)
CY(m-M1)
SP(1) SP(2)·····SP(N)
SP(1) SP(2)·····SP(N)
SP(1) SP(2)·····SP(N)
EB
f0
Source frequency

FIG. 6A

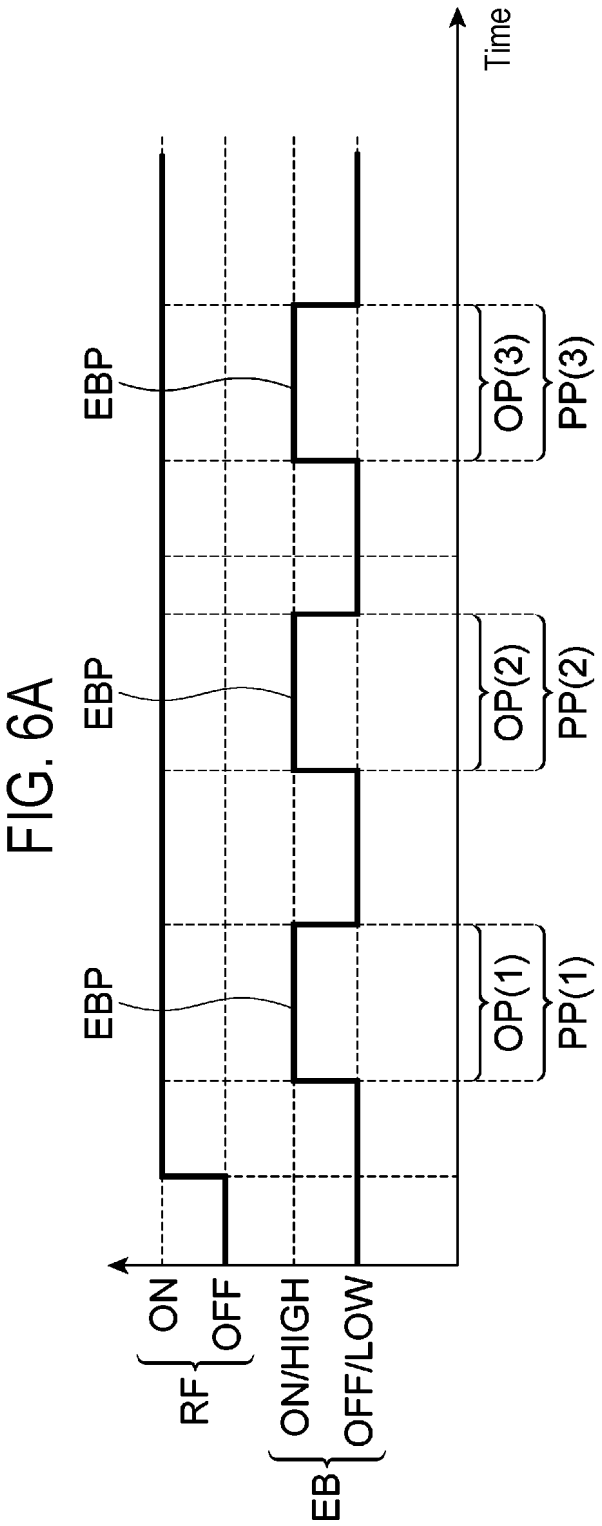

Time
EBP
EBP
EBP
OP(3)
PP(3)
OP(2)
PP(2)
OP(1)
PP(1)
RF
ON
OFF
EB
ON/HIGH
OFF/LOW

FIG. 6B

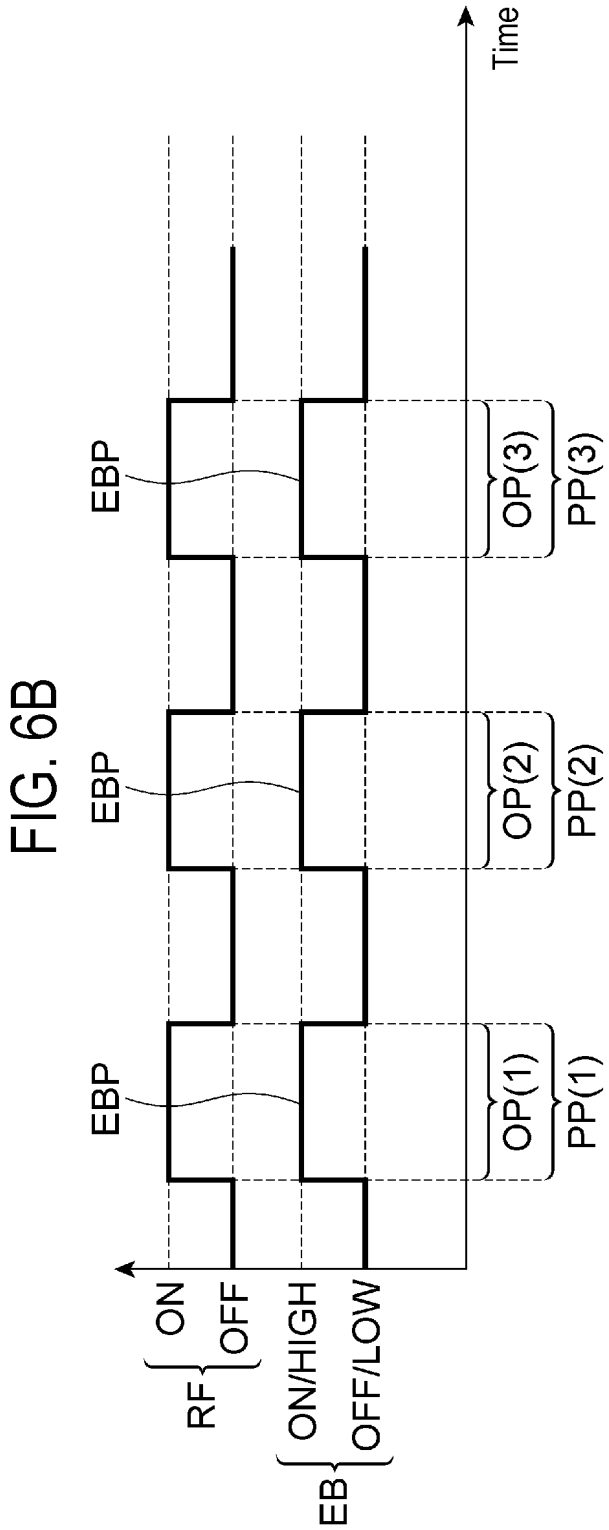

Time
EBP
EBP
EBP
OP(3)
PP(3)
OP(2)
PP(2)
OP(1)
PP(1)
RF
ON
OFF
EB
ON/HIGH
OFF/LOW

FIG. 7A

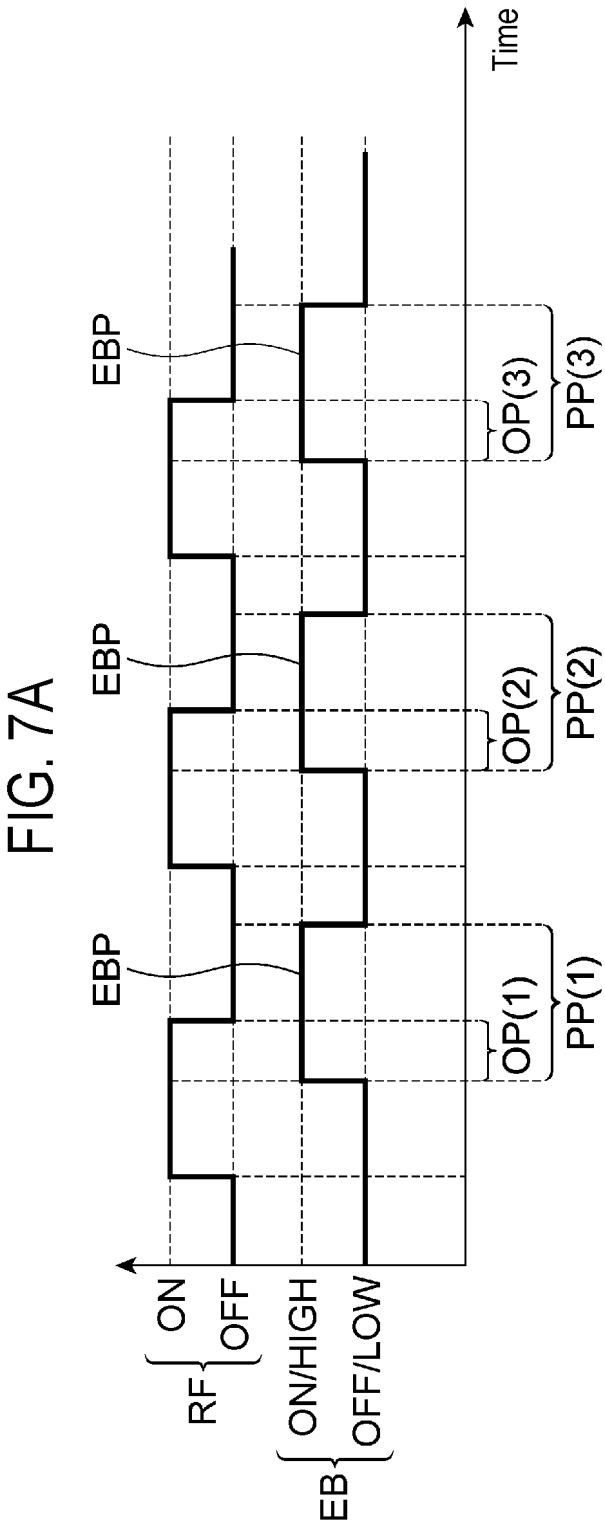

Time
EBP
EBP
EBP
OP(3)
OP(2)
OP(1)
PP(3)
PP(2)
PP(1)
RF
ON
OFF
EB
ON/HIGH
OFF/LOW

FIG. 7B

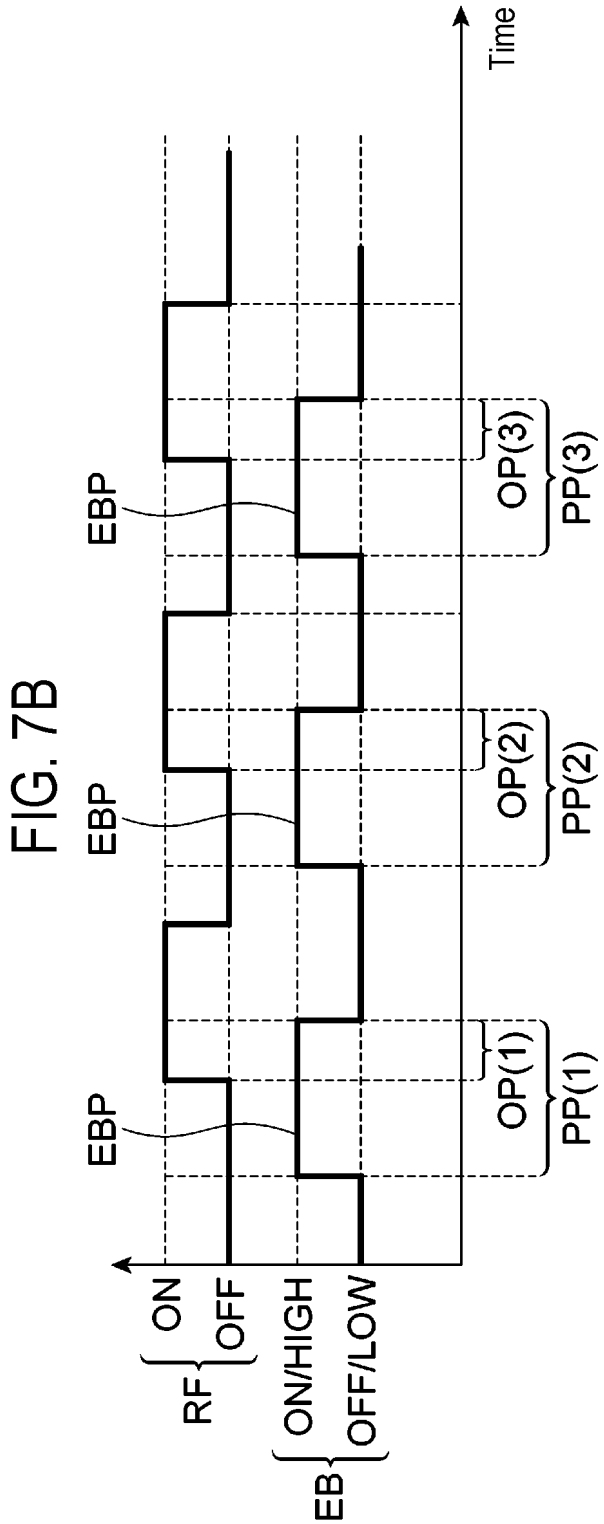

Time
EBP
EBP
EBP
OP(3)
PP(3)
OP(2)
PP(2)
OP(1)
PP(1)
RF
ON
OFF
EB
ON/HIGH
OFF/LOW

FIG. 8

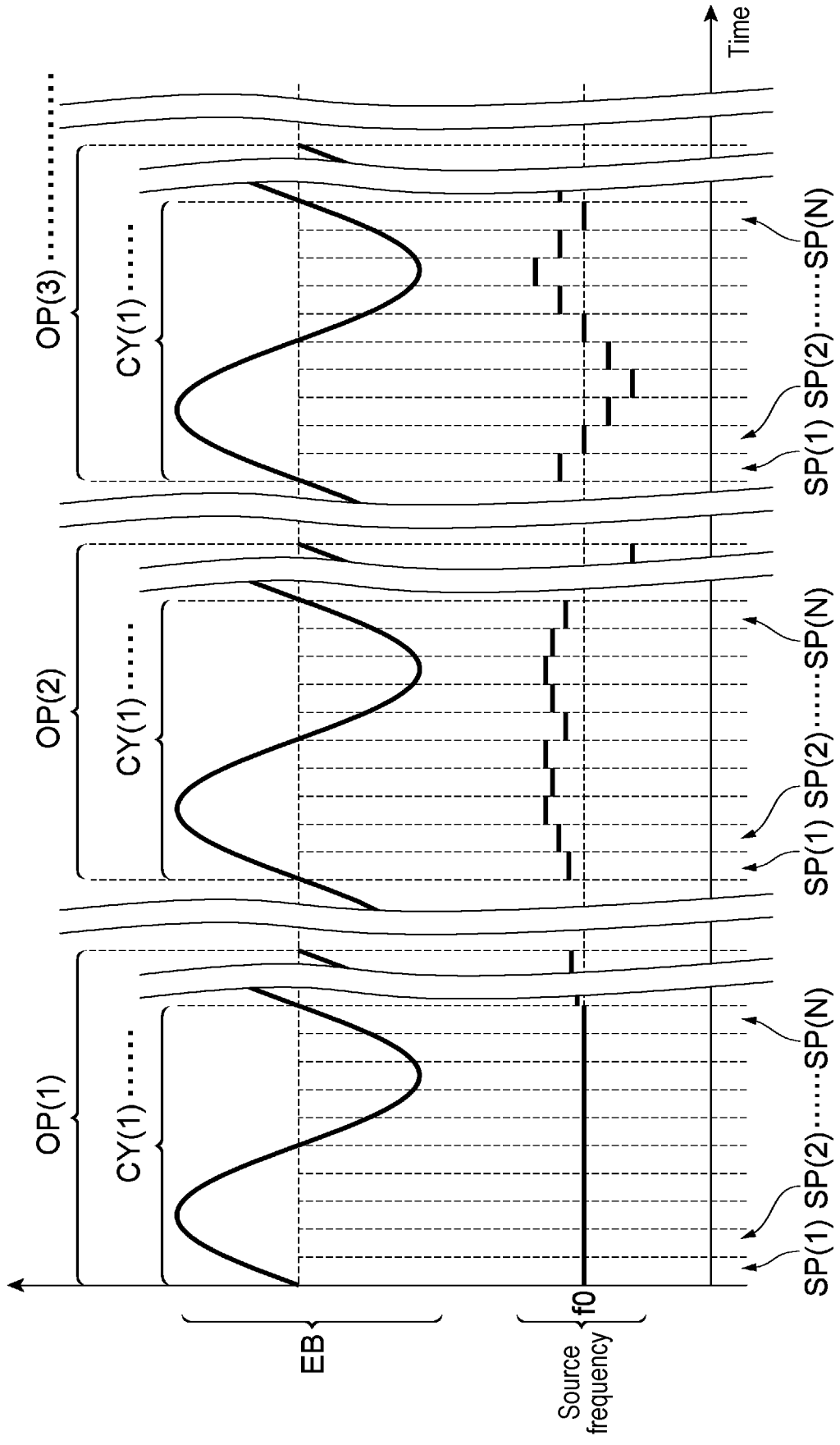

Time
OP(3)
CY(1)
OP(2)
CY(1)
OP(1)
CY(1)
SP(1) SP(2)……SP(N)
SP(1) SP(2)……SP(N)
SP(1) SP(2)……SP(N)
EB
f0
Source frequency

FIG. 9A

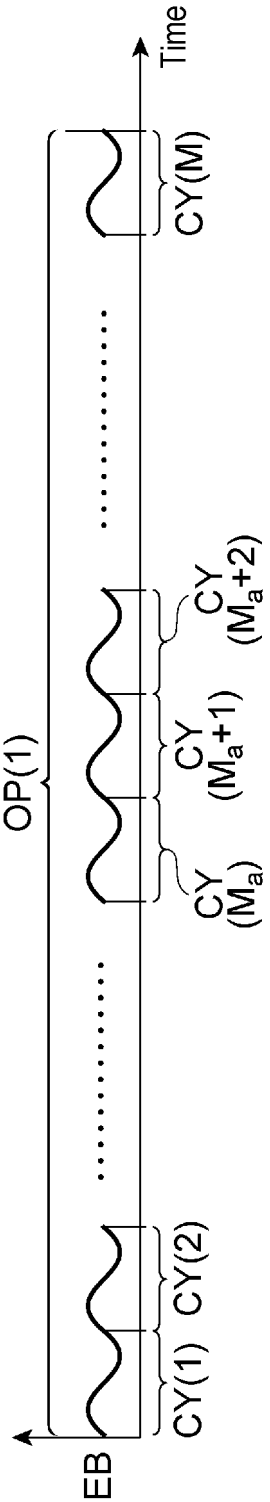


FIG. 9B

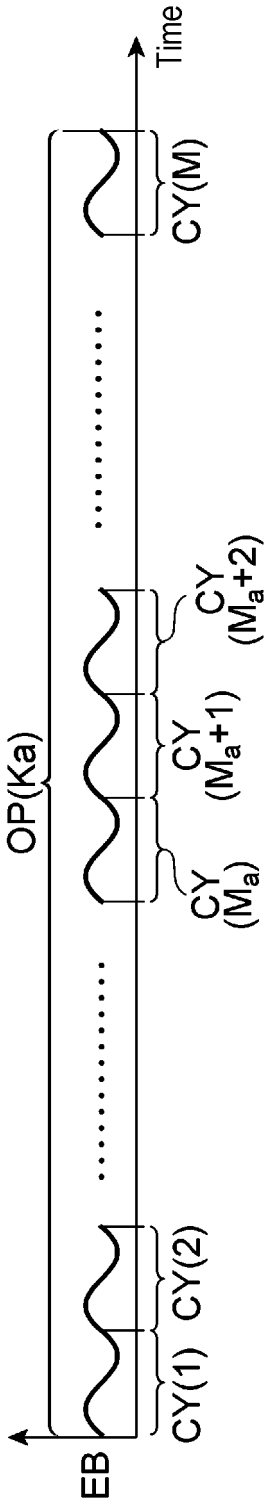


FIG. 9C

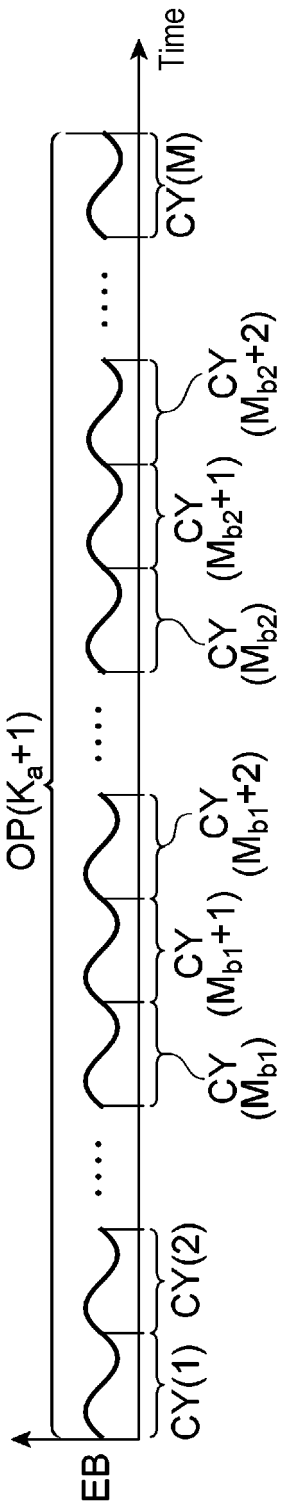

Time
EB
OP(Ka+1)
CY(1)
CY(2)
CY(M)
CY (Mb1)
CY (Mb1+1)
CY (Mb1+2)
CY (Mb2)
CY (Mb2+1)
CY (Mb2+2)

FIG. 9D

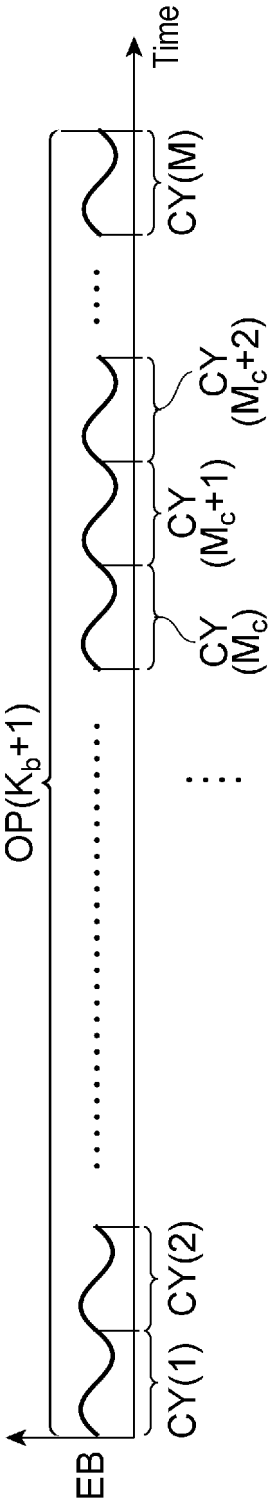
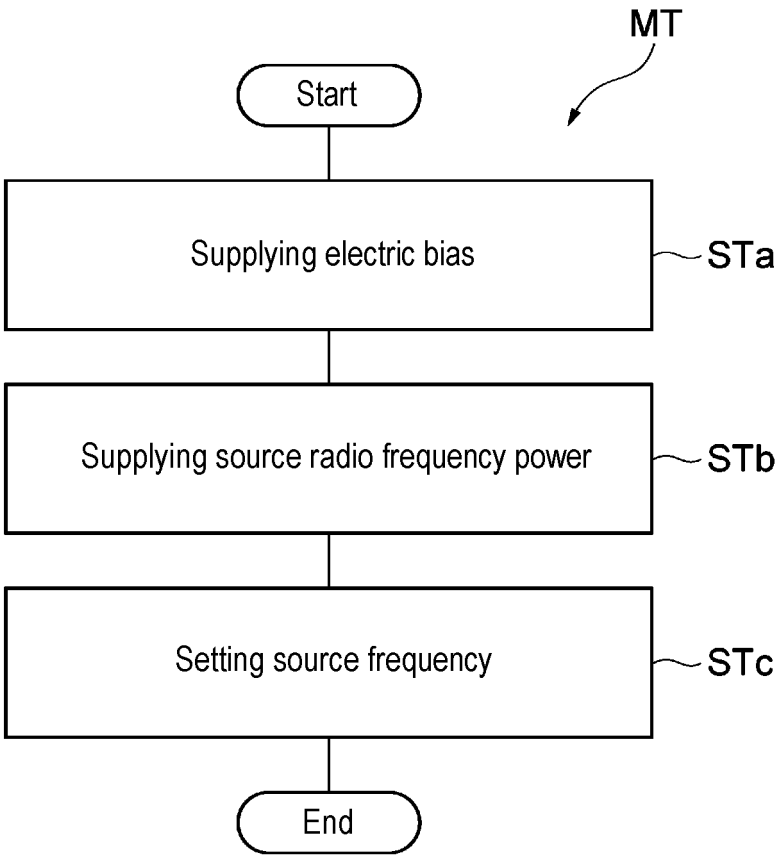


FIG. 10


MT
Start
Supplying electric bias
STa
Supplying source radio frequency power
STb
Setting source frequency
STc
End